

# Characterization of $\gamma$ -Al<sub>2</sub>O<sub>3</sub>/ $\beta$ -Ga<sub>2</sub>O<sub>3</sub> interface with photo-assisted capacitance-voltage method

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**[Introduction]**  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> is promising for next-generation power devices such as metal-oxide-semiconductor field-effect transistors (MOSFETs). In a MOSFET, trap states residing at interface between a channel and adjacent layers influence the performance and durability. According to the previous studies [1, 2],  $\gamma$ -Al<sub>2</sub>O<sub>3</sub> is prospected as a gate oxide for  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>-based MOSFET with good performance. Here we report on the electrical characterization of  $\gamma$ -Al<sub>2</sub>O<sub>3</sub>/ $\beta$ -Ga<sub>2</sub>O<sub>3</sub> interface with photo-assisted capacitance-voltage ( $C$ - $V$ ) method for accurate estimation of interface trap density ( $D_{it}$ ) [3].

**[Experiment]**  $\gamma$ -Al<sub>2</sub>O<sub>3</sub> epitaxial films were grown on unintentionally doped  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> (010) wafers by using oxygen-radical-assisted pulsed-laser deposition (PLD) at 500 °C. Then MOS capacitors were fabricated with semitransparent Au top electrodes and ITO bottom ohmic contacts. The current density-voltage ( $J$ - $V$ ) and the photo-assisted  $C$ - $V$  measurements were performed at RT with using a 300 W Xe lamp.

**[Results and discussion]** Figure 1 is the  $J$ - $V$  curve in dark exhibiting a high breakdown electric field more than 10 MV/cm. Figure 2 shows the results of photo-assisted  $C$ - $V$  measurement. There is a ledge in the curve after UV excitation. This ledge is attributed to retrapping of photoexcited electrons as the Fermi level reaches the deepest interface state. We calculated  $D_{it}$  from the voltage difference ( $\Delta V$ ) with respect to shifted dark curve (see Figs. 2 and 3). The peak at  $-0.5$  eV corresponds to holes accumulated at the valence band offset. The average  $D_{it}$  after subtracting this peak is  $2.0 \times 10^{12} \text{ cm}^{-2} \text{ eV}^{-1}$ , which is smaller than that of amorphous Al<sub>2</sub>O<sub>3</sub>/ $\beta$ -Ga<sub>2</sub>O<sub>3</sub> interface ( $5.5 \times 10^{12} \text{ cm}^{-2} \text{ eV}^{-1}$ ) estimated by the same method [4].

[1] M. Hattori *et al.*, *Jpn. J. Appl. Phys.* **55**, 1202B6 (2016).

[2] T. Kamimura *et al.*, *Jpn. J. Appl. Phys.* **55**, 1202B58 (2016).

[3] R. Yeluri *et al.*, *J. Appl. Phys.* **114**, 083718 (2013)

[4] Z. A. Jian *et al.*, *Appl. Phys. Lett.* **116**, 242105 (2020).

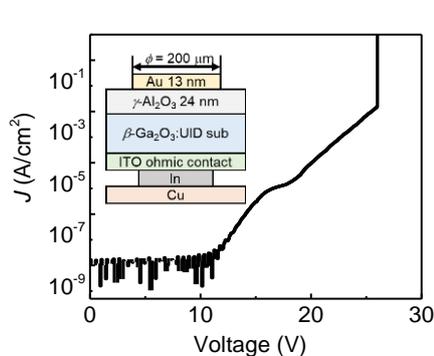


Fig. 1  $J$ - $V$  curve for a sample shown in inset.

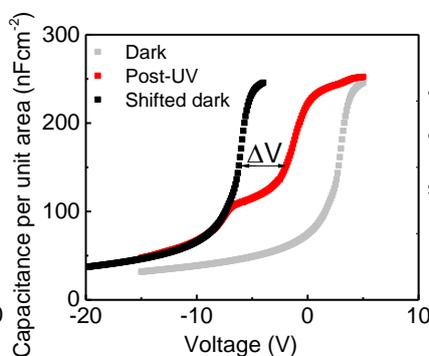


Fig. 2  $C$ - $V$  curves in dark (gray) and after UV photoexcitation for 15 s (red). The shifted dark curve (black) is also shown for clarity.

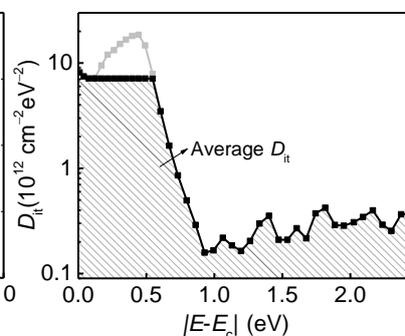


Fig. 3  $D_{it}$  as a function of energy with respect to the conduction band maximum  $E_c$ .